## REMARKS

Reconsideration and allowance of the above-referenced application are respectfully requested.

Claims 1-4 and 6-8 stand rejected under 35 U.S.C. 103(a) as allegedly being unpatentable over the admitted prior art in view of the Williams Patent No. 5,614,026. This contention is respectfully traversed.

Claim 1 defines a plasma CVD apparatus which has a gas that is introduced into the chamber for performing the plasma CVD, and exhausted through a plurality of openings provided in an electrode. This is similar to that shown in FIGS. 4A and 5.

The Examiner alleges that Williams discloses a shower head type system with concentric openings contained within the shower head for exhausting the gas. According to this interpretation, the Office Action alleges that it would have been obvious to one of ordinary skill in the art to modify the admitted prior art system to exhaust gas from the openings in the shower head, as shown by Williams.

However, this contention is respectfully traversed, and it is specifically noted that the claims require the openings being provided in the electrode which is not taught or suggested by Williams. This claimed electrode is used for supplying an electrical energy inside the vacuum chamber. Williams, on the other hand, does not teach that the shower head functions as an

electrode. Williams, in fact, teaches away from this system, since he teaches that the shower head is preferably constructed of an electrically non-conducting material (see column 6, lines 38-40). Williams teaches using a microwave plasma generator 302 that is located outside the processing chamber. Williams also teaches that the processing chamber can omit electrodes entirely. Accordingly, it appears that Williams teaches away from the use of the electrodes inside the chamber (see column 5, lines 18-33). As such, it would not be obvious to one of ordinary skill in the art to combine Williams with the device of the prior art, since Williams teaches away from the use of such electrodes. Moreover, even if these devices were combined, the Williams type system does not include openings in the electrode itself, and therefore, would not render obvious the subject matter of the present claims.

Claim 1 has been amended to obviate the rejection under Section 112.

In view of the above amendments and remarks, therefore, all of the claims should be in condition for allowance. A formal notice to that effect is respectfully solicited.

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No. 06-1050.

Respectfally submitted,

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## VERSION TO SHOW CHANGES MADE

## In the Claims:

Claim 1 has been amended as follows.

- 1. (Amended) A plasma CVD apparatus comprising:
- a vacuum chamber;

an introducing means for introducing a gas into the vacuum chamber;

an exhaust means for exhausting the gas from the vacuum chamber to an outside;

an electrode for supplying an electric energy inside the vacuum chamber;

a supporting means for supporting a substrate so that a surface of said substrate is opposed to [opposing] the electrode,

wherein an introducing port for introducing said gas is located adjacent to [an electrode side surface of] said surface of the substrate,

wherein [a plurality of openings are located on] a surface of the electrode opposing the substrate is provided with a plurality of openings,

wherein the gas is exhausted from the plurality of openings to the outside of the vacuum chamber.

\_\_ FISH & RICHARDSON P.C.

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New claims 9-19 have been added.